### Simulation and Measurement of the Shockley–Ramo Current from a Pixelated Silicon Detector

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## Shockley–Ramo Current

 $v_d$ 

Cf

R,

e-

+V.

Dphoto

 $\vec{\mathbf{I}}_{ir}$ 

- Shockley–Ramo current or the induced current at a readout electrode from the instantaneous change of electrostatic flux lines
  - $Q = \oint_{S} \epsilon E \cdot dS$
  - Signal is distinct from the drift current measured in traditional silicon detectors
  - Bipolar signal that will integrate to zero in a few nanoseconds
  - Current from a moving point charge can be expressed as
  - $i = E_v q v$  (Shockley-Ramo Theorem) **Fermilab** D. Berry



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### Advantages of Shockley-Ramo Current

- There a several advantages of measuring the induced current
  - Very fast rise time
    - Signal begins as soon as the electrostatic flux changes at the readout electrode
    - · No need to wait for the drift charge
  - Complex shape information
    - The shape of the induced current depends on the depth and position of the charge deposit
    - Angle of incidence information for charged particles

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### **Challenges of Shockley–Ramo Current**

- Small signal
  - Initial signal ~10% the size of the drift current's maximum amplitude
    - Requires a low threshold comparator
- Low Time Jitter

 $\sigma_t \approx \frac{C_L}{\sqrt{g_m t_a}} \frac{\sqrt{t_a^2 + t_d^2}}{signal} \qquad g_m = \frac{\Delta I_a}{\Delta V_i}$ 

- Requires a readout system with low capacitance and high front-end transconductance
  - Balance input current with pixel density and power/cooling limitations
- More details can be found in: R. Lipton and J. Theiman. "Fast timing with induced current detectors". In: Nucl. Instrum. Meth. A 945 (2019), p. 162423. doi: <u>10.1016/j.nima.2019.162423</u>.

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## Sensor Parameters

- Requires sensor with a large (~10) pixel-pitch to sensor thickness ratio
- Small pitched 25x25 µm pixels
  - Lower pixel capacitance
    - Low Noise
    - Fast rise time
- 200-300 µm thick silicon sensor
  - Drift and induced current is distributed on multiple pixels
- n-on-p design nominally used
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#### Biased 50µm sensor in TCAD



## **Sensor Simulation**

Sensor models built in TCAD MIP Deposit in 320µm Silicon

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- Two different signal types simulated
  - MIPs 4fC uniformly distributed through sensor
  - Point 4fC deposited at a specific depth
- No time walk or ionization fluctuations

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## **Readout Simulation**

- Front end amplifier simulated in SPICE
  - Transimpedance amplifier with feedback resistor
    - 500 MHz Gain Bandwidth
    - 65nm feature size
    - Transimpedance amplifier consumes ~4µA  $\sigma_t \approx \frac{C_L}{\sqrt{g_m t_a}} \frac{\sqrt{t_a^2 + t_d^2}}{signal} \quad g_m = \frac{\Delta I_a}{\Delta V_i}$
  - Noise and Landau fluctuations added to simulated signal from TCAD
    - Extracted noise induced jitter of ~16ps
  - ASIC will have to use 3D architecture to fit in 25µm pixel pitch
    - 3D integration will also minimize capacitive coupling

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PWL file=/Users/ronlipton/Dropbox/Timing/PULSE/D0\_T50\_E4.txt



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.step param mc1seed 1 50 1 .param pc\_elec=1.6e-7 .param lcs=5.2e-7\*Thick .param rm=5.31e7 .param gm=({ge}\*{ld})/(2\*{k}\*{T}) .param gm=.5 .param gsd=2\*{k}\*{T}\*{gam}/{gm} .param k=1.38066e-23 .param T=293 .param Id=.1e-6 .lib opamp.sub .param FMAX=1e9 .param tstep=1/(2\*{FMAX}) .param sig=sqrt({psd}\*{FMAX})

param ipsd=(4\*{k}\*{T}/{RF

param MPV=77.9\*Thick\*pc\_elec

aram Thick=50

.step param mcseed .tran {tstep} 15n

.noise V(n002) V(0) dec 100 100k 1000k

isig=sqrt({ipsd}\*{FMAX})

# Weighting Field

- Shockley-Ramo current directly proportional to the weighting field
  - $i = E_v q v$
  - The direction of the electric field in the direction of the drift particles velocity
    - Free charge depleted
    - Readout electrode at unit potential
    - · All other electrodes at ground
- The weighting field is highly dependent on pixel geometry



## Initial Shockley–Ramo Current

**Fast Current Edge** Shockley-Ramo current begins as drift charge starts moving Pixel 1 Pixel 2 Pixel 7 Very sharp rising edge Pixel 3 Pixel 8 Signal Amplitude (nA) 50 Pixel 4 Pixel 9 The central pixel time resolution is ~10ps Pixel 5 30 Low signal threshold 20 The initial Shockley-Ramo current amplitude is 2-14% of the maximum 0 signal amplitude Shape dependent on charge • 1.2 2.4 0.8 2.0 2.8 3.2 1.6 deposition location and depth Time (ns) Timing histogram Timing histogram Central pixel has larger 10-С initial current and better time resolution **Edge Electrode Central Electrode** σ~30 ps σ~10 ps 103.8 103.85 103.9 103.95 103.75102.2 102.4 102.6 102.8 Fermilab

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## Pixel Hit Pattern

- Shockley-Ramo current has a time dependent signal shape
  - Sums to 0 over a few nanoseconds
  - Only pixels that readout drift current will have a position charge integral
- Signal shape on neighboring pixels dependent on particles incident angle
  - Central and edge pixels receive different fractions of the drift and induced current



## **CMS Outer Tracker Trigger**

CMS is currently building a dual layer module to trigger at L1 on "high" p<sub>T</sub> tracks





## Angular Dependent Signal

- Charged particles with large incident angles have significant drift and Shockley-Ramo currents in neighboring pixels
- An ASIC with periodic current sampling could perform an on-chip angle measurement

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## Angular Variables

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- Investigating dedicated variables to extract angular information
  - Time to Maximum
  - Total relative amplitudes
  - Cluster width
    - Small (25µm) pixel-pitch
- Need ASIC to calculate simple quantities for triggering
  - Trigger could use multivariate (MVA) techniques
  - Possible to integrate MVAs into the ASIC as well



### **Proposed Measurement Setup**

**ETROC0** 

**ÉTROCO** Pre-Amp Inputs

- Novati Wafer with 30x100 µm pitch left over from an 8" wafer development project
- Possible to connect sensor to ETROCO
  - ETROC designed for LGAD sensor
  - Operating at the edge of the chips capabilities (~3 fC)
- Wire bonding seems to be the lowest capacitance connection scheme

#### Simulated ETROC Performance



## Measurement Setup

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- Novati wafer has a small contact area intended for bump bonds
  - 13µm bump bond pad
  - Investigated bump bond fanout
    - Parallel fanout lines will likely have excessive capacitance
  - Will be challenging to land a wire bond in such a small area





- Introduced a Shockley–Ramo current detector
  - Traditional silicon detector with large (~10) pitch-to-thickness ratio
    - Excellent time resolution (<20ps)</li>
    - Requires low capacitance readout chain
      - 3D integration
    - Small Signal Threshold
      - Pixel geometry can be adjusted to enhance weighting field
    - Has the capability to measure a particle's incident angle
      - Can be used to create a track trigger at Level-1
  - Simple bench setup in the works to detect Shockley-Ramo signal

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